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## **Wed-Af-Po3.18-06 [42]: Improvement of $J_c$ properties for Hf and La doped Gd123 films fabricated by fluorine-free MOD method**

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We have fabricated Hf and La doped FF-MOD GdBa<sub>2</sub>Cu<sub>3</sub>O<sub>y</sub> (Gd123) thin films on LaAlO<sub>3</sub> substrates and investigated their flux pinning properties. Temperature dependence of  $J_c$  in magnetic fields parallel to the c-axis orientation up to 7 T was estimated from the width of the magnetization curves using the modified critical state model. Critical temperature for Gd123 thin films indicated around 92 K, and  $T_c$  varied little by Hf and La doping. Hf 10 mol% doped film achieved high critical current densities of 2.72 MA cm<sup>-2</sup> at 77.3 K under 0 T, and 0.27 MA cm<sup>-2</sup> at 77.3 K under 1 T. With increasing Hf doping amount,  $F_p$  gradually increased, and the peak of  $F_p$  shifted to the high magnetic field side. The elementary pinning force and the effective pinning center density also increased. The number of effective pins increases until Hf 2 mol%, and then it decreases a little. Especially Hf 2 mol% film obtained the maximum value of 49.8  $\mu\text{m}^{-2}$  at 4.2 K, which is 2 times larger than that for non-doped film. We believe that BaHfO<sub>3</sub> are introduced into FF-MOD Gd123 thin films by Hf doping. Furthermore, Gd123 thin films with La addition showed the increase of  $J_c$  at self-magnetic fields and the decrease in number of density of holes on the film surface. La 1 mol% and Hf 2 mol% co-doped film achieved high critical current densities of 3.10 MA cm<sup>-2</sup> at 77.3 K under 0 T, and 0.32 MA cm<sup>-2</sup> at 77.3 K under 1 T. It confirmed that the effective APCs were introduced by Hf doping to improve  $F_p$  in magnetic fields and promoting crystallization of Gd123 by La doping brought about the increase of  $J_c$  in low fields.

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